



Attorney Docket No. 005950-844

Patent

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of
Zhanggao Liu et al.

Application No.: 10/764,407

Filing Date: January 23, 2004

Title: PHOTORESIST COMPOSITIONS COMPRISING DIAMONDROID DERIVATIVES

Group Art Unit: 1755

Examiner:

Confirmation No.: 9511

FIRST
INFORMATION DISCLOSURE STATEMENT
TRANSMITTAL LETTER

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Enclosed is a FIRST Information Disclosure Statement and accompanying form PTO-1449 for the above-identified patent application.

- ☒ No additional fee for submission of an IDS is required.
- ☐ The fee of \$180.00 (1806) as set forth in 37 C.F.R. § 1.17(p) is also enclosed.
- ☐ A statement under 37 C.F.R. § 1.97(e) is also enclosed.
- ☐ A statement under 37 C.F.R. § 1.97(e), and the fee of \$180.00 (1806) as set forth in 37 C.F.R. § 1.17(p) are also enclosed.
- ☐ Charge _____ to Deposit Account No. 02-4800 for the fee due.
- ☐ A check in the amount of _____ is enclosed for the fee due.
- ☐ Charge _____ to credit card. Form PTO-2038 is attached.

The Director is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

P.O. Box 1404
Alexandria, Virginia 22313-1404
(650) 622-2300

By

Stephen F. Powell

Stephen F. Powell

Registration No. 43,014

Date: 10-14-04

BURNS DOANE

BURNS DOANE SWECKER & MATHIS LLP
INTELLECTUAL PROPERTY LAW

FIRST
INFORMATION DISCLOSURE STATEMENT
TRANSMITTAL LETTER

(4/04)



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: Patent Application of

Shenggao Liu et al.

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For: PHOTORESIST COMPOSITIONS
COMPRISING DIAMOND
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FIRST INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In accordance with the duty of disclosure as set forth in 37 C.F.R. § 1.56, the accompanying information is being submitted in accordance with 37 C.F.R. §§ 1.97 and 1.98.

Pursuant to 37 C.F.R. § 1.98, a copy of each of the documents cited is enclosed. However, copies of the listed U.S. patents and U.S. patent application publications are not enclosed since it is no longer required according to the July 11, 2003 waiver of the requirement for copies of cited U.S. patents and U.S. patent application publications in national patent applications filed after June 30, 2003 and international applications entering the national stage under 35 U.S.C. § 371 after June 30, 2003.

The documents are being submitted within three (3) months of the filing or entry of the national stage of this application or before the first Office Action on the merits, whichever is later. Since these documents are being filed within the time period set forth in 37 C.F.R. § 1.97(b), no fee or statement is required.

FIRST Information Disclosure Statement

Application No. 10/764,407

Attorney's Docket No. 005950-844

Page 2

To assist the Examiner, the document is / documents are listed on the attached form PTO-1449. It is respectfully requested that an Examiner initialed copy of this form be returned to the undersigned.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

Date 10-14-04

By: Stephen F. Powell
Stephen F. Powell
Registration No. 43,014
Redwood Shores, California Office
(650) 622-2300

P.O. Box 1404
Alexandria, Virginia 22313-1404

Complete if Known

**FIRST
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

Sheet

3

Application Number	10/764,407
Filing Date	January 23, 2004
First Named Inventor	Shenggao Liu et al.
Examiner Name	
Attorney Docket Number	005950-844

U.S. PATENT DOCUMENTS

Examiner Initials	Document Number	Kind Code (if known)	Name of Patentee or Applicant of Cited Document	Issue/Publication Date (MM-DD-YYYY)
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 Examiner
Signature

 Date
Considered

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet 2 of 3

Complete if Known

Application Number	10/764,407
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Attorney Docket Number	005950-844

Sheet	3	of	3
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STATUS

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NON-PATENT LITERATURE DOCUMENTS

Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
	LIAW, Der-Jang, "Synthesis and characterization of new polyamides and polyimides prepared from 2,2-bis[4-(4-aminophenoxy)phenyl]adamantane," <u>Macromol. Chem. Phys.</u> 200. No. 6, pp. 1326-1332 (1999)
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Examiner Signature	Date Considered
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(Note: If citation is in conformance with M.P.E.P. § 609, Draw line through citation if not in)

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